

Sheet 1

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# INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant: Hisashi OHTANI et al.

Filing Date: February 27, 1997 Group: 2829

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
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## OFFICE OF PETITIONS

## FOREIGN PATENT DOCUMENTS

Document Number	Date	Country	Class	Subclass	Translation Yes No

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EP	/	Tamura et al., "Oriented Crystal Growth of Si on SiO <sub>2</sub> Patterns by Pulse Ruby Laser Annealing" Proceedings of the 12 <sup>th</sup> Conference on Solid State Devices, Tokyo (1980), pp. 43-48
EP	/	H. R. Wenk et al. "Texture Analysis of Polycrystalline Silicon Films" J. Appl. Phys. 67 (1) 1/1/1990 pp. 572-574
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EP	/	Yunosuke KAWAZU et al. "Low-Temperature Crystallization of Hydrogenated Amorphous Silicon Induced by Nickel Silicide Formation" Institute of Applied Physics, University of Tsukuba, pp.2698-2704 (10/20/1990)
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EP	/	Hiroyuki KURIYAMA et al. "Comprehensive Study of Lateral Grain Growth in Poly-Si Films by Excimer Laser Annealing and Its Application to Thin Film Transistors" Jpn. J. Appl. Phys., Vol. 33 (1994) pp. 5667-5662 (10/10/1994)

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